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PATENT
Attorney Docket No.: 00939B-068710US
Client Ref. No.: 99-OPH-1750/CIP/EYL

TOWNSEND and TOWNSEND and CREW LLP

By: Bonnie Rickles
Bonnie Rickles

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Jae Chang JUNG et al.

Application No.: 10/080,507

Filed: February 22, 2002

For: CROSS-LINKING MONOMERS
FOR PHOTORESIST, AND PROCESS
FOR PREPARING PHOTORESIST
POLYMERS USING THE SAME

Customer No.: 20350

Confirmation No. 1185

Examiner: Sin J. Lee

Technology Center/Art Unit: 1752

AMENDMENT

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action mailed January 23, 2006, please enter the
following amendments and remarks:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 5 of this
paper.

Remarks/Arguments begin on page 12 of this paper.